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On the other hand, the number of carbon fluoride groups is preferably larger than the number of alkyl groups when the stain resistant agent contains a terminal carbon fluoride group combining with the silicon-containing functional group and a terminal alkyl group combining with said silicon-containing functional group. Results of experiments conducted by the inventors show that this increases perfluoroalkylsilane, resulting in high scale, hairdye, wear and alkali resistances.

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**Page 9, please replace the paragraph spanning lines 13-17, with the following rewritten paragraph:**

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When the stain resistant treatment of the present invention is applied to a treated surface which has already been stained, a ceramic product to which no stain resistant treatment has been applied can be changed to a treated ceramic product, or the reduced stain resistant effect of the ceramic product can be improved.

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**Page 10, please replace the paragraphs spanning line 12 through page 11, line 28, with the following rewritten paragraphs:**

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FIGS. 1A and 1B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 1 respectively;

FIGS. 2A and 2B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 2 respectively;

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FIGS. 3A and 3B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 3 respectively;

FIGS. 4A and 4B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 4 respectively;

FIGS. 5A and 5B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 5 respectively;

FIGS. 6A and 6B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 6 respectively;

FIGS. 7A and 7B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 7 respectively;

FIGS. 8A and 8B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 8 respectively;

FIGS. 9A and 9B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 9 respectively;

FIGS. 10A and 10B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 10 respectively;

FIGS. 11A and 11B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 11 respectively;

FIGS. 12A and 12B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 12 respectively;

FIGS. 13A and 13B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 13 respectively;

FIGS. 14A and 14B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 14 respectively;

FIGS. 15A and 15B show a chemical formula of a stain resistant agent and a schematic structure of a layer comprising the stain resistant agent concerning test 15 respectively;

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**In the Claims:**

**Kindly cancel claims 11 and 24 presently in the application without prejudice.**

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**Kindly amend claims 1-10, 12, 14, 16, 17, 20, 22 and 23:**

1. (Amended) A sanitary chinaware intended to be repeatedly wetted and dried during use, said sanitary chinaware having a treated surface formed with a layer comprising a stain resistant agent, said agent including a silicon-containing functional group, previously combined, by